

## **SYSTEM AND METHOD FOR ETCHING RESIN WITH AN OZONE WET ETCHING PROCESS**

### **ABSTRACT OF THE INVENTION**

5           A method is provided for cleaning resin residue in liquid  
crystal display (LCD) or integrated circuit (IC) fabrication process.  
The method comprises: forming an electrode layer; forming an  
interlayer film of resin overlying the electrode later; patterning the  
resin interlayer; forming a via to access the first area of the electrode  
10 layer; in response to forming the via, forming a resin residue overlying  
a first area of the electrode layer; introducing a gas mixture including  
ozone into water to create a moist ozone gas, where the gas mixture is  
approximately 10 % ozone by molecular weight (wt %); wet ashing the  
resin residue overlying the first area of the electrode layer using the  
15 moist ozone gas; and, depositing a metal layer overlying the first area  
of the electrode to form a pixel electrode.